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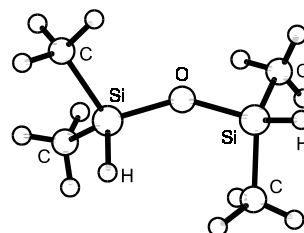
C₄H₁₄OSi₂

1,1,3,3-Tetramethyldisiloxane
Bis(dimethylsilyl) ether

C₁
(H₃C)₂HSi–O–SiH(CH₃)₂

r_a	\AA^a	θ_a	deg ^{a)}
Si–O	1.635(2)	O–Si–C	110.1(6)
Si–C	1.864(3)	C–Si–C	107.4(17)
C–H	1.117(3)	Si–C–H	109.0(7)
Si–H	1.490 ^{b)}	O–Si–H	109.5 ^{b)}
		Si–O–Si	148.4(9)
		τ_1 ^{c)}	101.3(84)
		τ_2 ^{c)}	–41.1(36)
		τ_3 ^{d)}	30.2(25)

The least-squares refinements were performed on the radical distribution curves. Small amounts of conformers other than that described cannot be ruled out. It was assumed that the Si(CH₃)₂ group had local C₂ symmetry. The measurements were made at room temperature.



^{a)} Estimated standard errors including a systematic error.

^{b)} Assumed.

^{c)} H–Si–O–Si twist angle; $\tau = 0^\circ$ when the Si–H bond is *syn* to the further O–Si bond.

^{d)} H–C–Si–O torsion angle; defined as zero when one C–H bond is eclipsed with respect to the Si–O bond.

Rankin, D.W.H., Robertson, H.E.: J. Chem. Soc., Dalton Trans. (1983) 265.